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## Guest Editorial: A Transition for JM<sup>3</sup>

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# Guest Editorial: A Transition for JM<sup>3</sup>

**Chris Mack**

Past Editor-in-Chief



I began as editor-in-chief of JM<sup>3</sup> in January of 2012, and after eight years serving in that role, I have stepped down as of January, 2020. The change brings a wealth of very mixed emotions. My time as editor-in-chief has been tremendously fun, but not without its challenges. I have learned a great amount: about being an editor, about the publishing business, and about how to write a good scientific paper. I will miss the engagement with the JM<sup>3</sup> community, especially with the highly professional SPIE staff and the dedicated volunteer senior editors and associate editors who do the bulk of the work to make JM<sup>3</sup> successful.

But these feelings of loss are tempered by my excitement about what will come next. Not only is there a new editor-in-chief of JM<sup>3</sup>, there are two! I'm extremely pleased to pass the baton on to Harry Levinson of HJL Lithography and Hans Zappe of the University of Freiburg. The choice of two co-editors-in-chief reflects the diversity of the JM<sup>3</sup> community. Harry comes from a semiconductor lithography and metrology background, while Hans has long worked in the areas of MEMS and MOEMS. Their combined strengths will undoubtedly prove extremely valuable in serving the needs of these different communities. Their charge is not to carry on, but to boldly look at possible new futures for their journal. I, for one, can't wait to see what they come up with!